

Amendments to the Claims

1. (Original): A substrate susceptor for receiving a substrate to be deposited upon, comprising:

a body having a substrate receiving side, the substrate receiving side comprising a face having a substrate receiving recess formed therein, the recess comprising an outer peripheral sidewall; and

at least three projections extending outwardly from a portion of the face, the projections respectively comprising a radially inner sidewall which extends outwardly from the recess outer peripheral sidewall to a projection upper surface.

2. (Original): The susceptor of claim 1 wherein the face portion is annular.

3. (Original): The susceptor of claim 1 wherein the face portion is substantially planar and continuous but for said projections.

4. (Original): The susceptor of claim 3 wherein the face portion is annular.

5. (Original): The susceptor of claim 1 wherein the substrate receiving recess is annular.

6. (Original): The susceptor of claim 5 wherein the face portion is annular.

7. (Original): The susceptor of claim 1 wherein the substrate receiving recess comprises a base, at least a portion of the recess outer peripheral sidewall extending perpendicularly from the recess base.

8. (Original): The susceptor of claim 7 wherein all of the recess outer peripheral sidewall extends perpendicularly from the recess base.

9. (Original): The susceptor of claim 1 wherein all said projections comprise a common shape.

10. (Original): The susceptor of claim 1 wherein said projections are each equally spaced on the face portion from immediately adjacent of said projections.

11. (Original): The susceptor of claim 1 wherein said projections are received about a circle on the face portion.

12. (Original): The susceptor of claim 11 wherein said projections collectively occupy less than 10% of the circumference of said circle.

13. (Original): The susceptor of claim 11 wherein said projections collectively occupy less than 5% of the circumference of said circle.

14. (Original): The susceptor of claim 11 wherein said projections collectively occupy less than 3% of the circumference of said circle.

15. (Original): The susceptor of claim 1 wherein said projections number no more than 8.

16. (Original): The susceptor of claim 1 wherein said projections number only 3.

17. (Original): The susceptor of claim 1 wherein said projections number only 4.

18. (Original): The susceptor of claim 1 wherein said projections number only 5.

19. (Original): The susceptor of claim 1 wherein said projections number only 6.

20. (Original): The susceptor of claim 1 wherein said projections number only 7.

21. (Original): The susceptor of claim 1 wherein said projections number only 8.

22. (Original): The susceptor of claim 1 wherein the body has an outermost peripheral edge and the projections respectively have an outmost peripheral edge, the projection outermost peripheral edge being received radially inward of the body outermost peripheral edge.

23. (Original): The susceptor of claim 1 wherein the projection upper surface is angled radially downward toward the substrate receiving recess.

24. (Original): The susceptor of claim 23 wherein the projection upper surface is angled radially downward toward the substrate receiving recess along a straight line in radial cross section.

25. (Original): The susceptor of claim 24 wherein the face portion is substantially planar but for said projections, the projection upper surface being angled at from 20° to 80° from the face portion.

26. (Original): The susceptor of claim 25 wherein the projection upper surface is angled at from 40° to 60° from the face portion.

27. (Original): The susceptor of claim 24 wherein the substrate receiving recess comprises a substantially planar base, the projection upper surface being angled at from 20° to 80° from the base.

28. (Original): The susceptor of claim 27 wherein the projection upper surface is angled at from 40° to 60° from the base.

29. (Original): The susceptor of claim 27 wherein the projection upper surface extends along a line in radial cross section having a radial extent of at least 5 mm.

30. (Original): The susceptor of claim 1 wherein the recess outer peripheral sidewall and the radially inner sidewall have a combined elevational length which is greater than thickness of a substrate for which the susceptor is designed.

31. (Original): The susceptor of claim 30 wherein the recess outer peripheral sidewall has an elevational length which is less than thickness of a substrate for which the susceptor is designed.

32. (Original): The susceptor of claim 30 wherein the recess outer peripheral sidewall has an elevational length which is equal to thickness of a substrate for which the susceptor is designed.

33. (Original): The susceptor of claim 1 wherein the recess outer peripheral sidewall and the radially inner sidewall have a combined elevational length which is equal to thickness of a substrate for which the susceptor is designed.

34. (Original): The susceptor of claim 1 wherein the recess outer peripheral sidewall and the radially inner sidewall have a combined elevational length which is less than thickness of a substrate for which the susceptor is designed.

35. (Original): The susceptor of claim 1 wherein the projection upper surface extends along a straight line in radial cross section.

36. (Original): The susceptor of claim 1 wherein the projection upper surface comprises a curved portion in radial cross section.

37. (Original): The method of claim 1 wherein the projection upper surface has an uppermost elevation which is received higher than an uppermost surface of a substrate for which the susceptor is designed when said substrate is received by said recess.

38. (Original): The method of claim 1 wherein the projection upper surface has an uppermost elevation which is received elevationally coincident with an uppermost surface of a substrate for which the susceptor is designed when said substrate is received by said recess.

39. (Original): The method of claim 1 wherein the projection upper surface has an uppermost elevation which is received elevationally lower than an uppermost surface of a substrate for which the susceptor is designed when said substrate is received by said recess.

40. (Original): The susceptor of claim 1 wherein at least a portion of the outer peripheral sidewall is angled radially downward toward the substrate receiving recess.

41. (Original): The susceptor of claim 40 wherein the substrate receiving recess comprises a base, a first portion of the recess outer peripheral sidewall extending perpendicularly relative to the recess base, a second portion of the recess outer peripheral sidewall extending from the first portion and being angled radially downward toward the substrate receiving recess.

42. (Original): The susceptor of claim 41 wherein the second portion extends along a line in radial cross section having a radial extent of at least 5 mm.

43. (Original): The method of claim 1 wherein the projection upper surface has an uppermost elevation which is received elevationally coincident with an uppermost surface of a substrate for which the susceptor is designed when said substrate is received by said recess.

44. (Original): The susceptor of claim 1 wherein the body has an outermost peripheral edge, the face spanning completely and continuously across the body within confines of the outermost peripheral edge.

Claims 45-153 (Canceled).